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ABSTRACT

A reticle (16) having a test pattern (TP) for measurement of an optical characteristic of a projection optical system (17) has a pattern adapted so that a high frequency component of a spectrum at a pupil plane (18) of the projection optical system (17) is reduced or suppressed. Illumination light is projected to the test pattern of the reticle (16) in one direction or plural directions, and positions of images of the test pattern (TP), formed by the projections in the plural directions, are detected and, based on it, the optical characteristic of the projection optical system (17) is measured.

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